# Teron™ SL670e

high performance reticle quality control system supports chip manufacturing by finding defects on EUV reticles that affect the yield of semiconductor chips

## BENEFITS:

Operating at industry-leading production throughput, the Teron SL670e provides high sensitivity detection of reticle defects that can affect chip yield, reliability and performance. The Teron SL670e helps chipmakers:

- Perform incoming quality control (IQC) of reticles shipped from mask manufacturers by validating that the reticles are free of particle and other potentially printable defects before they enter the chip manufacturing production stream
- Requalify reticles after multiple cycles of production use by providing actionable data on contamination or progressive defects so that reticles can be accurately dispositioned for cleaning or for continued production use

## TECHNOLOGIES:

- Defect sensitivity to support 7nm/5nm logic and advanced DRAM production
- Industry-best scan time
- Stringent cleanliness requirements for EUV production
- EUVGold™ and EUVMultiDie algorithms

## APPLICATIONS:

- Incoming reticle quality check
- Reticle requalification after production use or cleaning


## MARKETS:

### Chip manufacturing

EUV lithography applications including production of 7nm/5nm design node logic and advanced DRAM devices

## PLATFORM:

- Customizable configurations
- Extendible

## RETICLES:

- EUV reticles
- Option for advanced optical reticles

**MORE INFORMATION:** www.kla.com/products/reticle-manufacturing#teron-sl6xx